

CLAIMS

What is claimed is:

1. A method of producing a critical dimension value comprising:
 2. determining a stepper focus;
 3. combining said stepper focus with a critical dimension measurement; and
 4. generating said critical dimension value from said combining.
2. The method of claim 1, wherein said step of determining a stepper focus comprises:
 3. navigating to a stepper focus monitor target;
 4. performing a scanning electron microscope focusing; and
 5. performing a final alignment of said target.
1. 3. The method of claim 2, wherein said step of determining a stepper focus further comprises:
 3. acquiring a waveform data;
 4. analyzing said waveform data; and
 5. determining said stepper focus based on said analyzing.

1 4. The method of claim 2, wherein said step of determining a stepper focus further
2 comprises:

3 acquiring an image data;
4 analyzing said image data; and
5 determining said stepper focus based on said analyzing.

1 5. The method of claim 1, wherein said step of generating a critical dimension value
2 comprises:

3 navigating to a critical dimension structure;
4 performing a scanning electron microscope focusing; and
5 performing a final alignment of said structure.

1 6. The method of claim 5, wherein said step of generating a critical dimension value
2 further comprises:

3 acquiring a waveform data;
4 analyzing said waveform data; and
5 determining said critical dimension value based on said analyzing.

1 7. The method of claim 5, wherein said step of generating a critical dimension value
2 further comprises:

3 acquiring an image data;
4 analyzing said image data; and
5 determining said critical dimension value based on said analyzing.

1 8. A method of producing a critical dimension value comprising:
2 generating a scanning electron microscope focus;
3 generating a waveform data based on output from said scanning electron
4 microscope focus;
5 analyzing said waveform data to determine a critical dimension measurement;
6 analyzing said waveform data to determine a stepper focus parameter;
7 combining said stepper focus parameter with said critical dimension
8 measurement; and
9 generating said critical dimension value from said combining.

1 9. The method of claim 8, wherein said step of generating a waveform data further
2 comprises:
3 navigating to a critical dimension structure;
4 performing a scanning electron microscope focusing;
5 performing a final alignment of said structure; and

6 acquiring said waveform data based on said scanning electron microscope
7 focusing and said final alignment.

1 10. A method of producing a critical dimension value comprising:
2 generating a scanning electron microscope focus;
3 generating an image data based on output from said scanning electron microscope
4 focus;
5 analyzing said image data to determine a critical dimension measurement;
6 analyzing said image data to determine a stepper focus parameter;
7 combining said stepper focus parameter with said critical dimension
8 measurement; and
9 generating said critical dimension value from said combining.

1 11. The method of claim 10, wherein said step of generating an image data further
2 comprises:
3 navigating to a critical dimension structure;
4 performing a scanning electron microscope focusing;
5 performing a final alignment of said structure; and
6 acquiring said image data based on said scanning electron microscope focusing
7 and said final alignment.

1 12. A method of producing a critical dimension value comprising:
2 determining a stepper focus;
3 measuring a critical dimension measurement;
4 combining said stepper focus with said critical dimension measurement; and
5 generating said critical dimension value based on said combining.

1 13. The method of claim 12, wherein said step of determining a stepper focus

2 comprises:

3 navigating to a stepper focus monitor target;
4 performing a scanning electron microscope focusing; and
5 performing a final alignment of said target.

1 14. The method of claim 13, wherein said step of determining a stepper focus further

2 comprises:

3 acquiring a waveform data;
4 analyzing said waveform data; and
5 determining said stepper focus based on said analyzing.

1 15. The method of claim 13, wherein said step of determining a stepper focus further
2 comprises:

3 acquiring an image data;
4 analyzing said image data; and
5 determining said stepper focus based on said analyzing.

1 16. The method of claim 12, wherein said step of generating a critical dimension
2 value comprises:

3 navigating to a critical dimension structure;
4 performing a scanning electron microscope focusing; and
5 performing a final alignment of said structure.

1 17. The method of claim 16, wherein said step of generating a critical dimension
2 value further comprises:

3 acquiring a waveform data;
4 analyzing said waveform data; and
5 determining said critical dimension value based on said analyzing.

1 18. The method of claim 16, wherein said step of generating a critical dimension
2 value comprises:

3 acquiring an image data;
4 analyzing said image data; and
5 determining said critical dimension value based on said analyzing.

1 19. A method of producing a critical dimension value comprising:

2 determining a stepper focus;

3 measuring a critical dimension measurement;

4 combining said stepper focus with said critical dimension measurement; and

5 generating said critical dimension value based on said combining;

6 wherein said step of determining a stepper focus further comprises:

7 navigating to a stepper focus monitor target;

8 performing a scanning electron microscope focusing at said target;

9 performing a final alignment of said target based on said scanning electron

10 microscope focusing at said target;

11 acquiring a first data set from said scanning electron microscope focusing;

12 analyzing said first data set; and

13 determining said stepper focus based on said analyzing;

14 wherein said step of generating a critical dimension further comprises:

15 navigating to a critical dimension structure;

16 performing a scanning electron microscope focusing at said critical

17 dimension structure;

18 performing a final alignment of said critical dimension structure;

19 acquiring a second data set from said scanning electron microscope

20 focusing at said critical dimension structure;

21 analyzing said second data set; and

22 determining a critical dimension value based on said analyzing.

1 20. A program storage device readable by machine, tangibly embodying a program of
2 instructions executable by the machine to perform a method of producing a critical dimension
3 value, said method comprising:

4 determining a stepper focus;

5 combining said stepper focus with a critical dimension measurement; and

6 generating a critical dimension value from said combining.

1 21. The program storage device of claim 20, wherein said step of determining a
2 stepper focus comprises:

3 navigating to a stepper focus monitor target;

4 performing a scanning electron microscope focusing; and

5 performing a final alignment of said target.

1 22. The program storage device of claim 21, wherein said step of determining a
2 stepper focus further comprises:

3 acquiring a waveform data;

4 analyzing said waveform data; and

5 determining said stepper focus based on said analyzing.

1 23. The program storage device of claim 21, wherein said step of determining a
2 stepper focus further comprises:

3 acquiring an image data;
4 analyzing said image data; and
5 determining a stepper focus based on said analyzing.

1 24. The program storage device of claim 20, wherein said step of generating a critical
2 dimension value comprises:

3 navigating to a critical dimension structure;
4 performing a scanning electron microscope focusing; and
5 performing a final alignment of said structure.

1 25. The program storage device of claim 24, wherein said step of generating a critical
2 dimension value further comprises:

3 acquiring a waveform data;
4 analyzing said waveform data; and
5 determining said critical dimension value based on said analyzing.

1 26. The program storage device of claim 24, wherein said step of generating a critical
2 dimension value further comprises:

3 acquiring an image data;
4 analyzing said image data; and
5 determining said critical dimension value based on said analyzing.